

Abstract

The present invention relates to a method for writing a pattern on a surface intended for use in exposure equipment, including the steps of: arranging an object having a thickness (T) provided with a surface on a stage of a pattern generating apparatus, dividing the surface into a number of measurement points, where two adjacent measurement points being spaced a distance (P) apart not exceeding a predetermined maximum distance, determining the gradient of the surface at each measurement point, calculating a 2-dimensional local offset (d) in the x-y plane for each measurement point as a function of the gradient, and the thickness (T) of object, and correcting the pattern to be written on said surface by using the 2-dimensional local offset (d). The invention also relates to a method for measuring the physical properties of a surface.